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APPUCATION NO. 09/050, 113	FILING DATE	FIRST NAME	D INVENTOR	τ •εΛ	TORNEY DOCKET NO.
ARMSTRONG WES MCLELAND & NA 1725 K STREET SUITE 1000 WASHINGTON DC	UGHTÖN NW	MM21/0402 TORI	٦	ABT UNIT	PAPER NUMBER
				DATE MAILED:	

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

Office Action Summary

Application No. 09/050,113

Applicant(s)

Ema

Examiner

Carl Whitehead, Jr.

Group Art Unit 2815

Responsive to communication(s) filed on 1 Jul 1998	<u> </u>		
☐ This action is FINAL .			
 Since this application is in condition for allowance except in accordance with the practice under Ex parte Quayle, 19 	for formal matters, prosecution as to the merits is closed 935 C.D. 11; 453 O.G. 213.		
A shortened statutory period for response to this action is set is longer, from the mailing date of this communication. Failur application to become abandoned. (35 U.S.C. § 133). Exter 37 CFR 1.136(a).	re to respond within the period for response will cause the		
Disposition of Claims			
	is/are pending in the application.		
Of the above, claim(s) 16-34	is/are withdrawn from consideration.		
Claim(s)	is/are allowed.		
☐ Claim(s)			
Application Papers See the attached Notice of Draftsperson's Patent Draw			
The drawing(s) filed on is/are objection			
☐ The proposed drawing correction, filed on	is _approved _disapproved.		
☐ The specification is objected to by the Examiner.			
☐ The oath or declaration is objected to by the Examiner.	•		
Priority under 35 U.S.C. § 119			
Acknowledgement is made of a claim for foreign priori			
	s of the priority documents have been		
☑ received.	l what		
received in Application No. (Series Code/Serial N			
☐ received in this national stage application from the	ne international buleau (FC) nule (7.2(a)).		
*Certified copies not received: Acknowledgement is made of a claim for domestic prid	ority under 35 U.S.C. § 119(e)		
•	sitty under 33 3.3.6. 3 113(a).		
Attachment(s)			
☒ Notice of References Cited, PTO-892☒ Information Disclosure Statement(s), PTO-1449, Paper	No(s) 2		
☐ Interview Summary, PTO-413	110(3).		
☐ Notice of Draftsperson's Patent Drawing Review, PTO-	-948		
☐ Notice of Informal Patent Application, PTO-152			
SEE OFFICE ACTION OF	N THE FOLLOWING PAGES		

Appli ati n/C ntrol Numb r: 9/050,113

Art Unit: 2815 Non-final rej ction

DETAILED ACTION

This Office action is in response to the election and amendment filed 1 July 1998.

Election/Restriction

Applicant's election without traverse of the group I invention in Paper No. 5 is acknowledged.

Claims 15 to 34 are withdrawn from further consideration by the Examiner, 37 CFR 1.142(b) as being drawn to a non-elected invention. Election was made without traverse in Paper No. 5.

Title

The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1 to 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Uehara et al. in view of Hayden.

Uehara discloses a semiconductor device having a base (10), two conductor patterns (50b), a protective etch stopper film covering the upper surface of the patterns (18x), a first insulation film (32), a contact hole between the two conductor patterns (figure 6), sidewall insulation films (20a and 20b) and a plug buried in the contact hole (50a). The etch stopper film is made out of a conductive layer.

Uehara does not call the protective layers etch stop films, however this does not distinguish the invention over the cited art. Hayden also discloses the use of sidewalls and a protective layer on conductive

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patterns (figure 7). Hayden refers to his protective layer as an etch

stop layer (20). It would have been obvious to one of ordinary skill in

the art to modify the device of Uehara by incorporating an etch stop

layer to protect the structural integrity of conductor patterns, since

the technology was well known at the time the invention was made.

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to (703) 308-

4940.

Primary Patent Examiner

Semiconductor Technology

CW

March 28, 1999 ⁶